ECE 3030: Physical Foundations of Computer Engineering

Fall 2021

Homework 5—Total points 100

Due on Thursday 10/29/2021 at 11.59am. In case of a late submission, you will be penalized by 50 points for each day after the submission deadline has passed. You will receive no score if you submit after the solution has been posted.

- Q1 Band diagrams of a MOS capacitor for three different values of the gate voltage V_G are shown in figure 1. V_t is its threshold voltage. All the variables shown in figure 1 have their usual meanings. [30 pts]
 - [Q1.1] Based on the information provided in figure 1, find out whether V_G larger or smaller than V_t for each of the three cases. Briefly explain your answer. [10 pts]
 - [Q1.2] Find out the values of electron density and hole density at x=0 and x=60 nm for each of the three cases. Assume that $N_C=N_V=10^{25}~/\mathrm{m}^3$, $kT=25~\mathrm{meV},~E_G=1.1~\mathrm{eV}$ (all variables have their usual meaning). [20 pts]

Solution to Q1:

If
$$E_{FS} - E_i(x = 0) > \phi_B$$
, $V_G > V_t$.

If
$$E_{FS} - E_i(x = 0) = \phi_B$$
, $V_G = V_t$.

If
$$E_{FS} - E_i(x = 0) < \phi_B, V_G < V_t$$
.

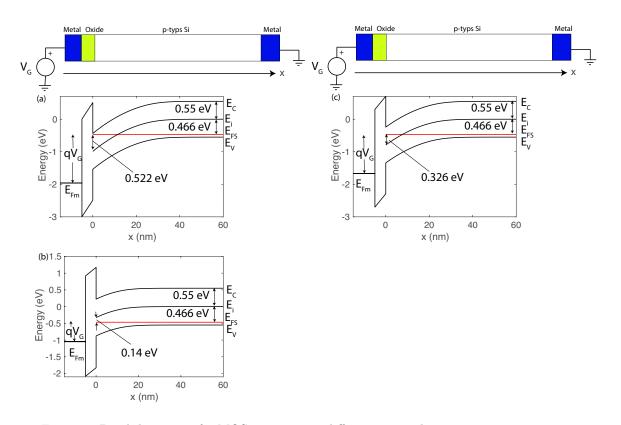


Figure 1: Band diagrams of a MOS capacitor at different gate voltages.



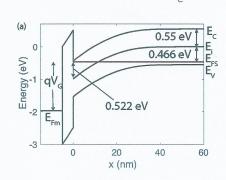


Figure 3: Band diagrams of a MOS capacitor at different gate voltages.

$$\frac{\chi=0}{E_{c}(\chi=0)} = \frac{E_{c}(\chi=0)}{E_{c}(\chi=0)} = 0.55 - 0.522 = 0.028 \text{ eV}$$

$$\frac{E_{c}(\chi=0)}{E_{c}(\chi=0)} = 0.55 + 0.522 = 1.072 \text{ eV}$$

$$\frac{E_{c}(\chi=0)}{E_{c}(\chi=0)} = \frac{E_{c}(\chi=0)}{E_{c}(\chi=0)} = \frac{E$$

Atternatively,
$$N^* = N_c e^{-Eg/2kT} = 10^{25} e^{-\frac{11}{2} \times \cdot 025} = 2.79 \times 10^{5} = 0.79 \times 10^{5} = 0.79$$

$$2=60 \text{ nm} \qquad \frac{E_{c}(z=60 \text{ nm}) - E_{FS} = 0.55 + 0.466 = 1.016 \text{ eV}}{E_{FS}(z=60 \text{ nm}) = 0.55 - 0.466 = 0.084 \text{ eV}}$$

$$-\frac{E_{c}(z=60 \text{ nm}) - E_{FS}}{kT} = \frac{1.016}{0.025} = 2.24 \times 10^{7} \text{ m}^{-3}$$

$$p(z=60 \text{ nm}) = N_{c} = \frac{E_{FS} - E_{v}(z=60 \text{ nm})}{3} = 10^{5} = \frac{0.084}{0.025} = 3.47 \times 10^{23} \text{ m}^{-3}$$

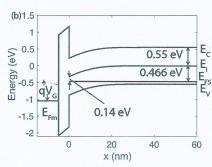


Figure 4: Band diagrams of a MOS capacitor at different gate voltages.

$$n(x=0)=N_ce \frac{E_c(x=0)-E_{ps}}{k\Gamma}$$

$$= 10^{25}e^{-\frac{0.69}{.025}}$$

$$= 1.03 \times 10^{13} \text{ m}^3$$

$$P(x=0) = P(x=0) = 0.55eV - 0.14eV = 0.41eV$$

$$P(x=0) = N_c e \frac{E_c(x=0) - E_{ps}}{kT}$$

$$P(x=0) = N_c e \frac{E_c(x=0) - E_{ps}}{kT}$$

$$= 10^{25} e \frac{0.69}{0.025}$$

$$= 7.54 \times 10^{17} m^3$$

alternatively:
$$E_1(x=0)-E_{PS}$$

 $n(x=0)=N^*e$
 $E_1(x=0)-E_{PS}$
 $p(x=0)=N^*e$
 $E_1(x=0)-E_{PS}$
 $E_1(x=0)-E_1(x=0)$
 $E_1(x=0)-E$

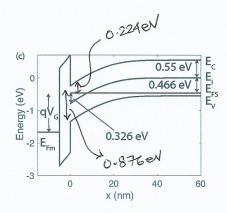


Figure 5: Band diagrams of a MOS capacitor at different gate voltages.

EPS - E1 (x=0) = 0.326 eV < PB VG < VE

$$2 = 0 \text{ nm} : E_{e}(\alpha = 0) - E_{FS} = 0.55 - 0.326 = 0.224 \text{ eV}$$

$$E_{FS} - E_{V}(\alpha = 0) = 0.55 + 0.326 = 0.876 \text{ eV}$$

$$= \frac{E_{e}(\alpha = 0) - E_{FS}}{E_{FS}}$$

$$= \frac{E_{e}(\alpha = 0) - E_{FS}}{E_{FS}} = 0.55 + 0.326 = 0.224 \text{ eV}$$

$$= \frac{E_{FS}}{E_{FS}} - E_{V}(\alpha = 0)$$

$$= \frac{876}{0.025}$$

$$= 10^{35} \text{ e} \frac{.876}{0.025}$$

$$= \frac{.925}{0.025}$$

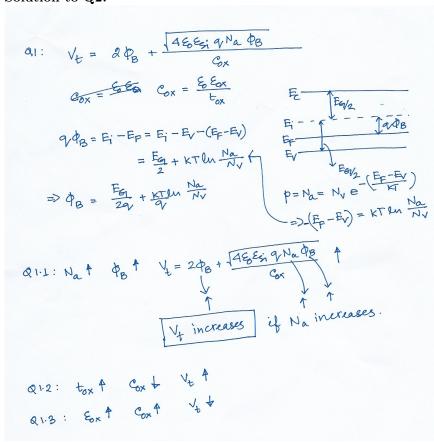
$$= \frac{6.05 \times 10^{9} \text{ m}^{3}}{10^{3}}$$

alternatively:

$$\chi = 60 \text{ nm} \cdot \text{E} \cdot \frac{326}{1000} = \frac{326}{100$$

- Q2 In class, we have derived an expression for the threshold voltage V_t in an n-type MOSFET. How does V_t change if the following parameters are increased. [25 pts]
 - Q2.1 Acceptor doping density, N_a .
 - Q2.2 Oxide thickness, t_{ox} .
 - Q2.1 Dielectric constant of oxide, ϵ_{ox} .

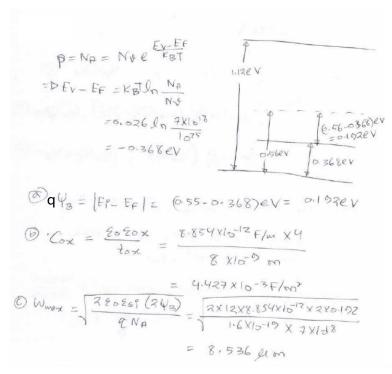
Solution to Q2:



Q3 Consider an n-type MOSFET with N_A =7×10¹⁸ m³. The gate length of the MOSFET L=2 μ m, width W=12 μ m and the oxide thickness t_{ox} = 8 nm. Take N_C = N_V =10²⁵ m³, E_G =1.12 eV, n_i =1.5×10¹⁶ m³, kT=0.026 eV, vacuum permittivity ε_{\circ} =8.854×10⁻¹² F/m, dielectric constant of oxide ε_{ox} =4, dielectric constant of silicon ε_{Si} =12, electron mobility μ_n =230×10⁻⁴ m²/Vs, hole mobility μ_p =83 ×10⁻⁴ m²/Vs.

Calculate $\phi_B = |E_F - E_i|/q$, the oxide capacitance C_{ox} , the maximum depletion width W_{max} and the threshold voltage V_t . [25 pts]

Solution to Q3:



$$V_{t} = \sqrt{42.02512 \text{ NA } \text{ VB}} + 24B$$

$$= \sqrt{4 \times 8.854 \times 15^{12} \times 12 \times 1.6 \times 10^{-19} \times 7 \times 15^{8} \times 0.152}$$

$$= 4.2 \times 0.152$$

$$= 0.386 \text{ V}$$

Q4 Draw the band diagram for n-type semiconductor (V_g is gate voltage and V_{th} is threshold voltage). [20 pts]

Q4.1 when $V_g = 0$

Q4.2 when $V_g > V_{th}$

Q4.3 when $V_g \leq V_{th}$

Solution to Q4:

n-type semiconductor look the same as for p-type with reverse the unequal signs in the voltage conditions. $V_g > V_{th}$ is depletion for n-type semiconductor $V_g < V_{th}$ is inversion for n-type semiconductor.

